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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of :  
Jun HATAKEYAMA et al. : Examiner: Rosemary E. Ashton  
Serial No.: 09/842,114 : Art Unit: 1752  
Filed: April 26, 2001 :  
For: POLYMER, CHEMICALLY AMPLIFIED RESIST COMPOSITION AND  
PATTERNING PROCESS

**REPLY UNDER 37 CFR §1.116**

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Office Action dated July 29, 2004, please amend the application as follows and consider the remarks.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 20 of this paper.